Toshiyuki Oyama

List of Publications by Year
in descending order

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38	562	567247	642715
papers	citations	15	23
		h-index	g-index

38	38	38	479
all docs	docs citations	times ranked	citing authors

#	Article	IF	Citations
1	Photosensitive fluorinated polyimides with a low dielectric constant based on reaction development patterning. Journal of Polymer Science Part A, 2003, 41, 861-871.	2.3	61
2	Structural characterization of cellulose nanofibers isolated from spent coffee grounds and their composite films with poly(vinyl alcohol): a new non-wood source. Cellulose, 2020, 27, 5017-5028.	4.9	40
3	Polymer Homologue of DMSO:Â Synthesis of Poly(ethylene sulfoxide) by Selective Oxidation of Poly(ethylene sulfide). Macromolecules, 1999, 32, 5240-5242.	4.8	38
4	Synthesis and positive-imaging photosensitivity of soluble polyimides having pendant carboxyl groups. Journal of Polymer Science Part A, 2001, 39, 934-946.	2.3	36
5	Photosensitive polycarbonates based on reaction development patterning (RDP). Polymer Bulletin, 2001, 47, 175-181.	3.3	30
6	Modification of cyanate ester resin by soluble polyarylates. Polymer International, 2003, 52, 773-782.	3.1	29
7	Low viscosity and high toughness epoxy resin modified by in situ radical polymerization method for improving mechanical properties of carbon fiber reinforced plastics. Polymer, 2018, 156, 1-9.	3.8	28
8	Modification of bismaleimide resin by soluble poly(ester imide) containing trimellitimide moieties. Polymer International, 2004, 53, 1417-1425.	3.1	26
9	Synthesis of Highly Optically Active Polysulfoxides by Asymmetric Oxidation of Polysulfides. Macromolecules, 1999, 32, 7732-7736.	4.8	25
10	Photocurable ABA triblock copolymer-based ion gels utilizing photodimerization of coumarin. RSC Advances, 2018, 8, 3418-3422.	3.6	19
11	Polystyrenes with chiral phosphoramide substituents as Lewis base catalysts for asymmetric addition of allyltrichlorosilane: enhancement of catalytic performance by polymer effect. Chemical Communications, 2005, , 1857.	4.1	18
12	Lithographic design of photosensitive polyarylates based on reaction development patterning. Journal of Polymer Science Part A, 2006, 44, 2694-2706.	2.3	18
13	Photosensitive Polyesterimides Based on Reaction Development Patterning. Polymer Journal, 2007, 39, 129-137.	2.7	18
14	Development of highâ€performance epoxy/clay nanocomposites by incorporating novel phosphonium modified montmorillonite. Journal of Applied Polymer Science, 2011, 122, 666-675.	2.6	18
15	A Novel Mechanism to Afford Photosensitivity to Unfunctionalized Polyimides: Negative-tone Reaction Development Patterning. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2009, 22, 597-602.	0.3	16
16	Photo-crosslinking of polystyrenes having pendant epoxy groups. Reactive and Functional Polymers, 2001, 49, 99-116.	4.1	15
17	Ionic-bonded negative photosensitive polyimides having pendant aminoalkyl (meth)acrylamide groups. Reactive and Functional Polymers, 2003, 56, 59-73.	4.1	13
18	Development of chemically amplified reaction development patterning. Polymer Journal, 2010, 42, 86-94.	2.7	13

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19	Examination of Pattern-forming Conditions in Negative-tone Reaction Development Patterning. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2009, 22, 407-410.	0.3	11
20	Effect of Maleimide Compounds on Pattern-forming Property of Photosensitive Polyimide Based on Negative-tone Reaction Development Patterning. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2010, 23, 141-144.	0.3	10
21	Development of Photosensitive Alicyclic Polyimides Based on Reaction Development Patterning. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2013, 26, 357-360.	0.3	10
22	Development of Thermostable Photosensitive Polycarbonates based on Negative-tone Reaction Development Patterning. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2010, 23, 511-514.	0.3	9
23	Toughening of Epoxy Resin by Modification with Poly[poly(N-phenylmaleimide-alt-styrene)-graft-polyethylene oxide]Prepared by in situ Polymerization. Kobunshi Ronbunshu, 2008, 65, 562-572.	0.2	8
24	Photosensitive Sulfonated Polyimides utilizing Alkaline-developable Negative-tone Reaction Development Patterning. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2011, 24, 269-272.	0.3	8
25	Curing Behavior and Thermal Mechanical Properties of Epoxy Resins Containing Polyaromatic Backbones. Kobunshi Ronbunshu, 2011, 68, 62-71.	0.2	7
26	Development of Photosensitive Vinyl Polymers with Imide Group Based on Reaction Development Patterning. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2012, 25, 371-374.	0.3	7
27	Curing acceleration of cyanate ester resin by a phenolic compound having a tertiary amino group at the ortho-position. Polymer Journal, 2020, 52, 1245-1252.	2.7	7
28	Positive-tone Pattern Formation from Vinyl Polymers with Maleimide Group by Reaction Development Patterning. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2011, 24, 523-526.	0.3	6
29	Addition of Photosensitivity to Hyperbranched Engineering Plastics based on Reaction Development Patterning. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2014, 27, 219-222.	0.3	6
30	Application of Biomass-Derived Lignophenol to Epoxy Resins. Kobunshi Ronbunshu, 2010, 67, 497-505.	0.2	5
31	Toughening of Acid Anhydride-cured Epoxy Resin by Modification with Poly[poly(N-phenylmaleimide-alt-styrene)-block-polyoxyethylene] Prepared by in situ Polymerization. Kobunshi Ronbunshu, 2006, 63, 720-726.	0.2	3
32	Heat-resistant photoresists based on new imaging technique: reaction development patterning (RDP). , 2003, 5039, 960.		1
33	Heat-resistant photoresists based on new imaging technique: reaction development patterning. Journal of Micro/ Nanolithography, MEMS, and MOEMS, 2004, 3, 159.	0.9	1
34	Study on Polybenzoxazine Modified with Epoxy Resin. Journal of Japan Institute of Electronics Packaging, 2011, 14, 204-211.	0.1	1
35	Addition of Photosensitivity to Engineering Plastics by a Novel Pattern-forming Method using Reactions of the Polymers with Developers: Reaction Development Patterning. Yuki Gosei Kagaku Kyokaishi/Journal of Synthetic Organic Chemistry, 2010, 68, 802-813.	0.1	1
36	Synthesis of Novel Reactive Polymers Having Oxirane Structure in the Main Chain by Polycondensation of Bis(sulfonium ylide) with Dialdehyde. Polymer Journal, 2004, 36, 737-746.	2.7	0

#	Article	IF	Citations
37	Toughening of Amine-cured Epoxy Resins by in situ Generated Poly(benzyl methacrylate). Kobunshi Ronbunshu, 2009, 66, 217-224.	0.2	0
38	Development of Novel Engineering Plastics Based on Reaction Development Patterning. Kobunshi Ronbunshu, 2010, 67, 477-488.	0.2	0